

## CLAIMS:

1. An electrophoretic display panel (11) comprising one or more pixels (20;42) comprising a fluid with dispersed charged particles (30) and a polymer wall (21;44) enclosing the fluid.
- 5 2. The electrophoretic display panel (11) according to claim 1, wherein said display panel (11) comprises electrodes (31) for said pixels (20;42) and said polymer wall (21;44) extends between said electrodes (31).
- 10 3. The electrophoretic display panel (11) according to claim 1, wherein said display panel (11) comprises electrodes (31) for said pixels (20;42) and said display panel (11) is substantially free of said dispersed charged particles (30) between said electrodes (31).
- 15 4. The electrophoretic display panel (11) according to claim 1, wherein said electrophoretic display panel (11) comprises a substrate (46), said substrate (46) and said polymer wall (44) being integrally formed.
5. A display device (10) comprising an electrophoretic display panel (11) according to claim 1 and circuitry to provide image information to said display panel (11).
- 20 6. A method for manufacturing an electrophoretic display panel (11) comprising - one or more pixels (20;42) comprising the steps of: providing a material system comprising a fluid with dispersed charged particles (30) and a photo-polymerizable substance; - exposing one or more selected portions of said material system to radiation to form a polymer wall (21;44) enclosing the fluid by polymerizing said photo-polymerizable substance.
- 25 7. The method according to claim 6, further comprising the steps of forming an electrode structure (31) on or over said material system to define said selected portions and

exposing said selected portions of said material system to said radiation to form said polymer wall (21;44).

8. The method according to claim 6, further comprising the steps of positioning  
5 said dispersed charged particles (30) by applying a voltage to define said selected portions and exposing said thus defined selected portions of said material system to said radiation to form said polymer wall (21;44).

9. The method according to claim 6, wherein said material system comprises a  
10 solvent and exposing to said radiation is performed at a temperature wherein said solvent is in a liquid crystalline state.

10. The method according to claim 6, wherein said material system further  
comprises polymerisation-inhibitors.

15 11. The method according to claim 6, further comprising the steps of providing  
said material system on or over a substrate (22;40) and forming a counter-substrate (46) from  
said material system by exposure of said material system to radiation.

20 12. The method according to claim 6, further comprising the steps of providing  
said material system on or over a substrate (22;40), irradiating said material system with a  
first radiation beam (43) to form said polymer wall and irradiating said material system with  
a second radiation beam (45) to form a counter-substrate (46).